

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

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Title of Invention

CRITICAL AREA COMPUTATION OF COMPOSITE FAULT
MECHANISMS USING VORONOI DIAGRAMS

Application Number :

Confirmation Number:

First Named Applicant: Robert Allen

Attorney Docket Number: BUR920030136US1

Art Unit:

Examiner:

Search string: (6178539 or 6247853 or 6317859).pn

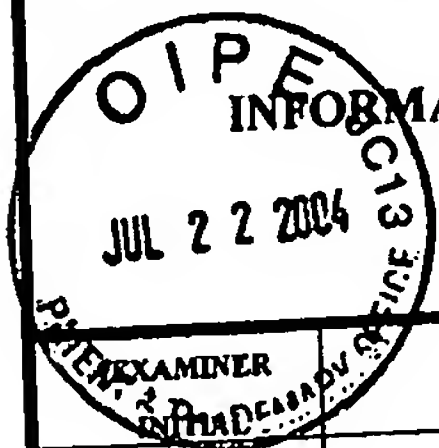
US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
SP	1	6178539	2001-01-23	Papadopoulou et al.			
SP	2	6247853	2001-06-19	Papadopoulou et al.			
SP	3	6317859	2001-11-13	Papadopoulou et al.			

Signature

Examiner Name	Date
<i>Eushin Parihar</i>	4-20-06



INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)
BUR920030136US1

Application Number
10/709293

Applicant(s)
Allen et al.

Filing Date
4-27-04

Group Art Unit
Unknown

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Papadopoulou, E. and Lee, D.T., "Critical area computation via Voronoi diagrams," Computer-Aided Design of Integrated Circuits and Systems, IEEE Transactions on , Vol. 18, No. 4, pp .463-474, April 1999.

Papadopoulou, E., "Critical area computation for missing material defects in VLSI circuits," Computer-Aided Design of Integrated Circuits and Systems, IEEE Transactions on , Vol. 20, No. 5, pp 583-597, May 2001.

Fook-Luen Heng and Zhan Chen. "VLSI Yield Enhancement Techniques Through Layout Modification." IBM T. J. Watson Research Center, pp. 1-15, July 17, 2000.

A. Venkataraman and I. Koren. "Trade-offs between Yield and Reliability Enhancement." Proc. of the 1996 IEEE National Symposium on Defect and Fault Tolerance in VLSI Systems, pp. 67-75, November 1996.

EXAMINER

Suchin Parihar

DATE CONSIDERED

4-20-06

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.